

LOCTITE ABLASTIK ICP2120 DATAPKG

-WGQ LAB

VINCE CAO, SKYLAR WU, CAROL LIU JUL 2022



PRODUCT DESCRIPTION

Application

- ❖ Low temp/moisture curable ECA for CCM bracket grounding.

Adhesion interface

- ❖ SUS, Ni

Advantages

- ❖ Excellent DCR and VR performance
- ❖ RT temp cure (≥ 3 days) or Lower curing temp(50C 30mins)
- ❖ High thermal conductivity
- ❖ Low tensile Modulus



Musashi syringe



Transparent piston

AGENDA

- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test



MATERIAL PROPERTY MATRIX

Item	Description	ICP2120	ABP2032s
Technology		Silicone	Epoxy
Filler type		Silver	Silver
Good dispense	Brookfield CP51,25°C, mPa.s(cP), Speed 5.0rpm	28000	11000
	TI	2.5	4.5
Worklife	@25C (hours)	24hrs	24hrs
Curing profile		0.5hr@50C/RT 3days	1hr@80C
Tacky Free	23C 50% RH (mins)	20	-
Thermal Conductivity	W/(m-K)	7	3-4
DMA	25C/100C/250C(Mpa)	900/284/311	4651/1204/322
Volume Resistivity Thickness 30um	25C 50%RH 24hrs (ohm-cm)	0.00006	
	50C 0.5hr bake (ohm-cm)	0.00015	0.0002(80C 1hr)
	50C 0.5hr bake+24hrs (ohm-cm)	0.00007	
DSS (2*2mm Si on substrate)	SUS304 sub / 50C 30mins(Mpa)	1.2	37(80C 1h)
	SUS304 sub / 72hrs(Mpa)	5	
Shelf life	-40C, days	180	365

AGENDA

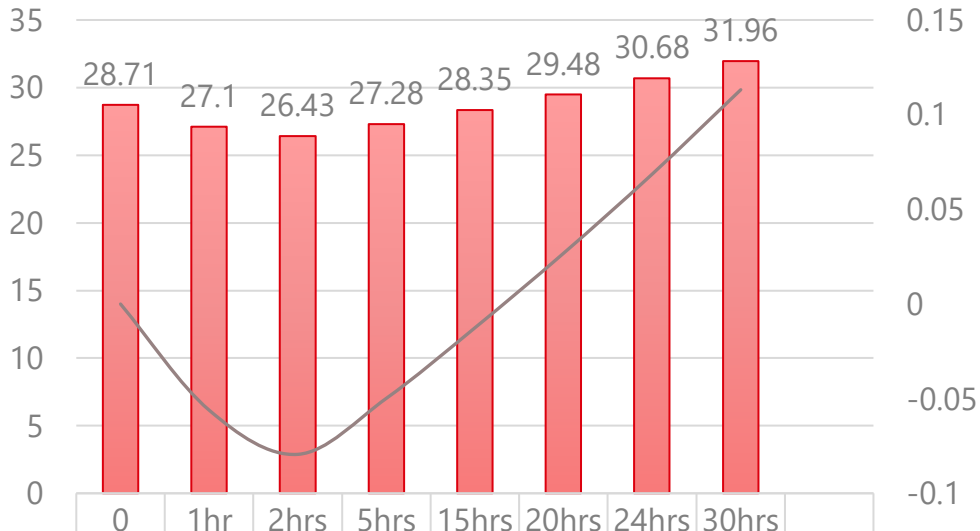
- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test



WORK LIFE STUDY

VISCOSITY TEST DATA

worklife of ICP2120



20 S-1 [Pa.S]	28.71	27.1	26.43	27.28	28.35	29.48	30.68	31.96
Ti	1.89	1.95	1.98	1.94	1.87	1.84	1.86	1.83
Variation	0	-5.6%	-7.9%	-5.0%	-1.3%	2.7%	6.9%	11.3%

Parameter

ICP2120 viscosity work life criterion

- Under room temperature 25C
- Rheometer 20S⁻¹ test data
- Viscosity increasement <25%

Summary

- Viscosity in 24hrs <25%
- To cover various customer's environment ,recommend work life 24hrs

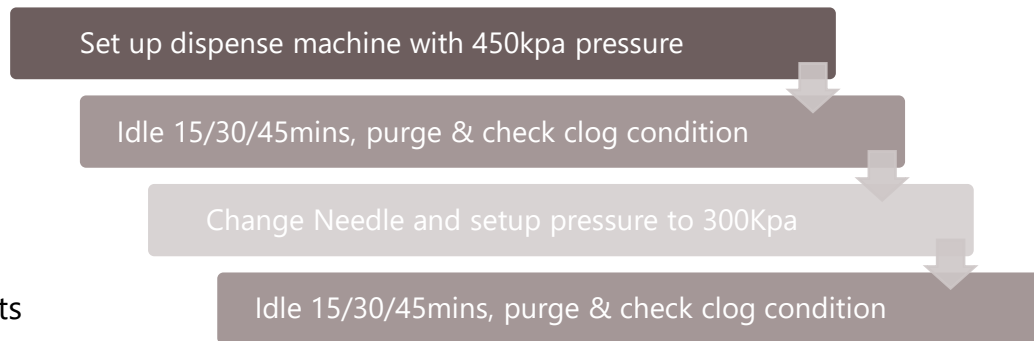
WORK LIFE STUDY

DISPENSING TEST DATA

Test parameter:

- Dispenser: Musashi PC350
- Needle: EFD G25 1/4inch, 0.25mm ϕ
- Lab environment: 25C/55%RH
- Test pressure: 300/450Kpa
- Test data: needle dispensing clog test with time points
- Test time point: 15/30/45mins

Test Flow:



Test summary: No clog issue within 45mins machine idle time > 300kpa pressure on EFD G25 needle

Machine	Pressure	Needle size	15mins	30mins	45mins
Musashi PC350	300KPa 450KPa	EFD G25, 0.25mm	No clog	No clog	No clog

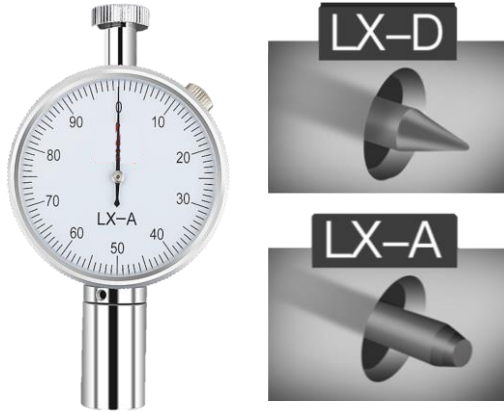
AGENDA

- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test



ADHESIVE CURED HARDNESS TEST ENVIRONMENT

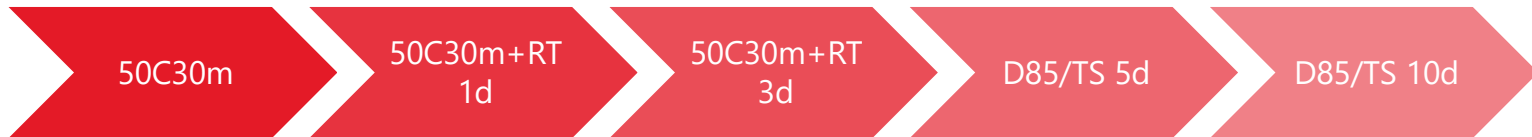
Shore hardness detector



Test parameter:

- Sample size: 10mmφ+ 3~4mm thickness
- Thermal cure:50C/30mins
- Test data: Shore A/D
- Room temp cure: 1/3days 25C/55RH%
- HTHH/D85: 85C/85RH%
- TS: -40C 30mins+85C 30mins /cyc

Thermal cure test procedure

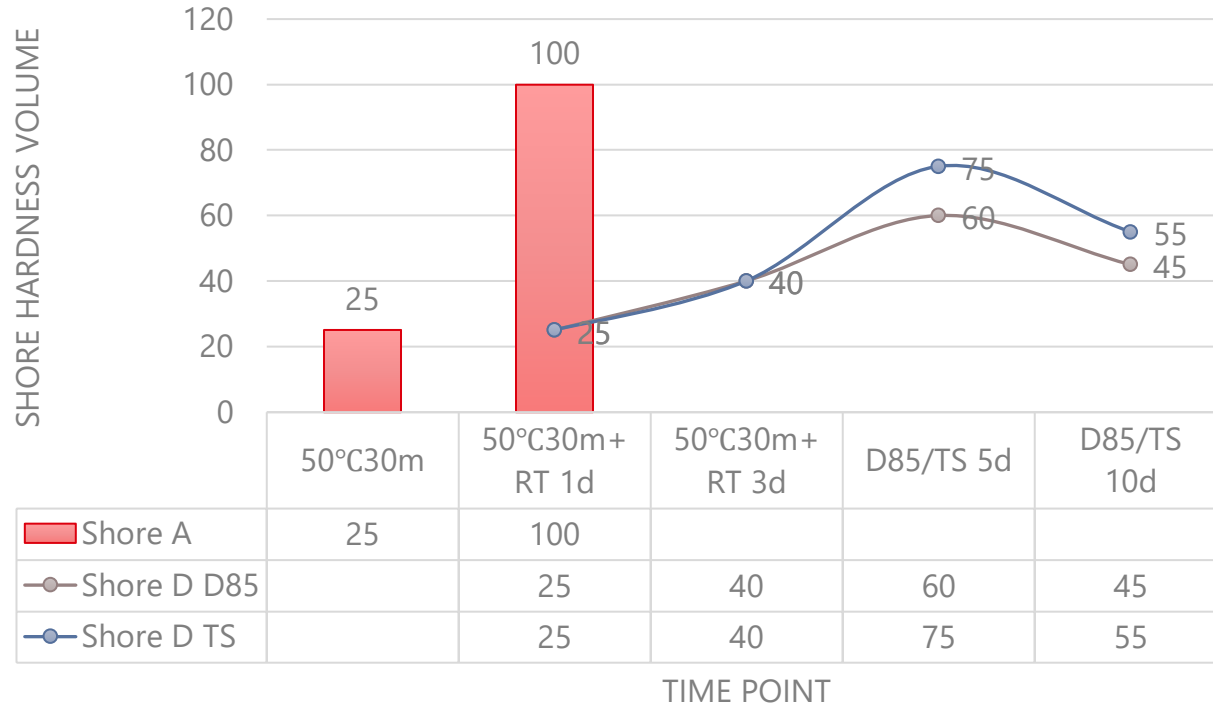


RT cure test procedure



ADHESIVE CURED HARDNESS WITH THERMAL

ICP2120 thermal cure shore hardness map



Summary

Curing stage

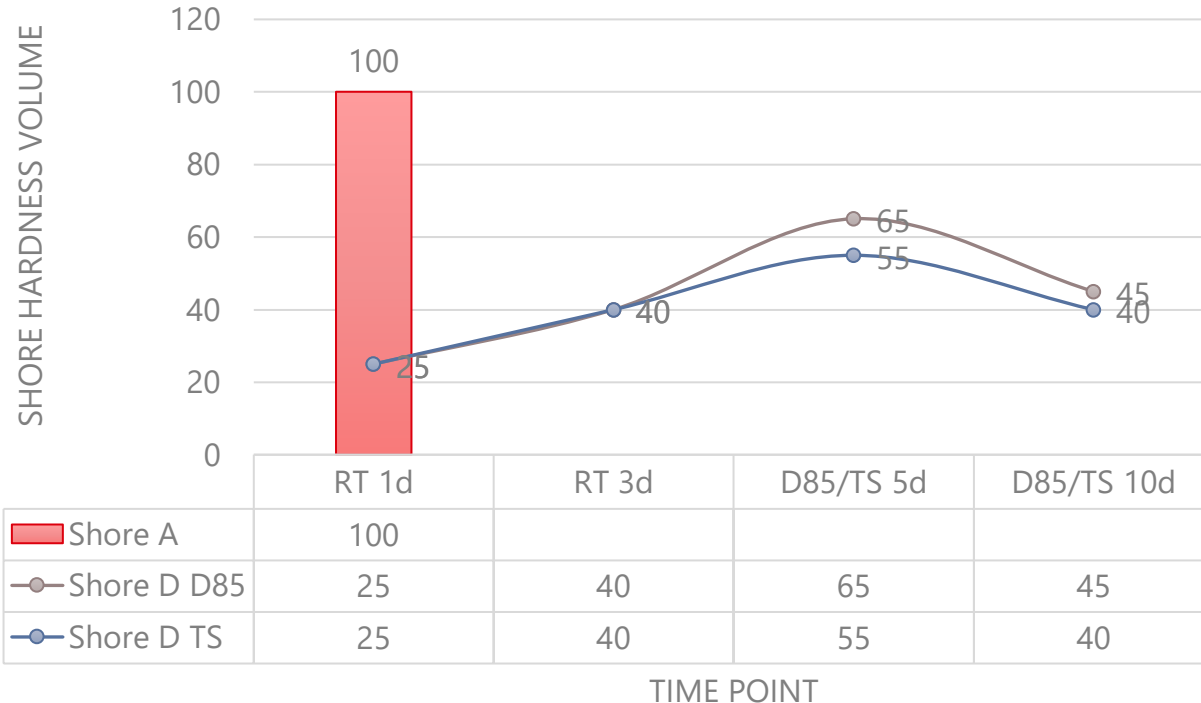
- ICP2120 curing with thermal, shore hardness data continues increase from shore A25 to D40

RA stage

- ICP2120 shore hardness achieve peak @5days, then goes down slowly.

ADHESIVE CURED HARDNESS WITH ROOM TEMPERATURE

ICP2120 RT cure shore hardness map



Summary

Curing stage

- ICP2120 curing with RT, shore hardness data continues increase from shore A100/D25 to D40

RA stage

- ICP2120 shore hardness achieve peak @5days, then goes down slowly.

AGENDA

- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test

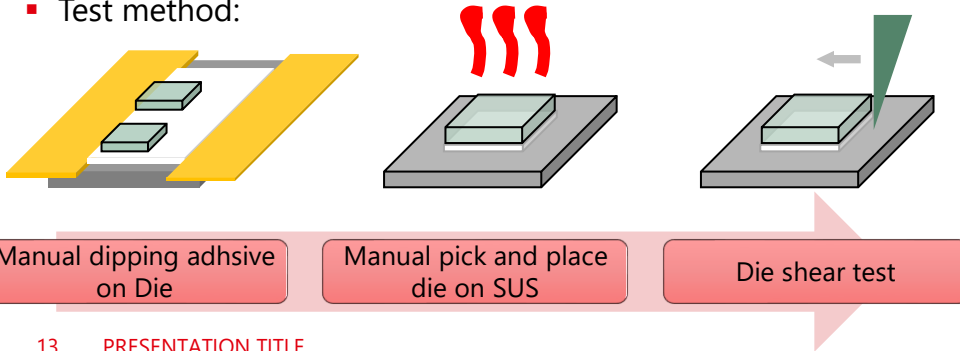


CURING PROFILE STUDY

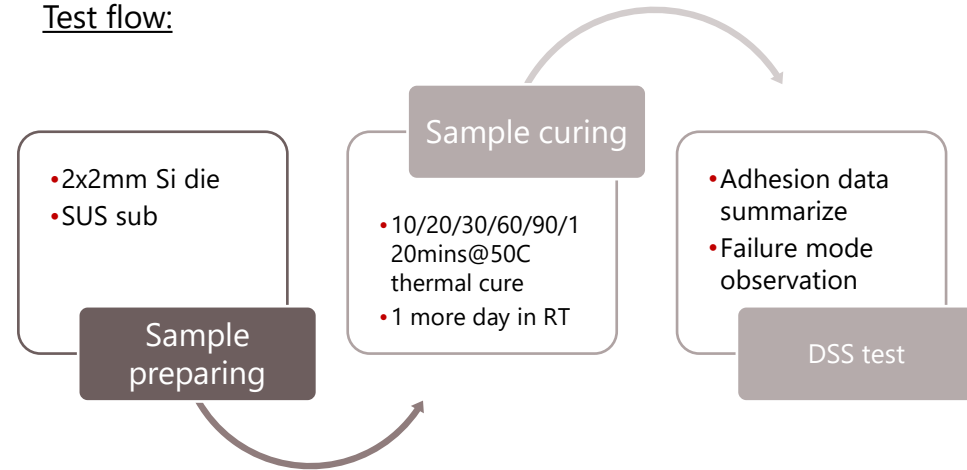
TEST PARAMETER AND FLOW

Test parameter:

- Die size: 2*2mm Si die(370um thickness)
- Substrate: SUS without plasma
- BLT: 30-40um
- Test data: Adhesion with different profiles
- Curing profiles: 10/20/30/60/90/120mins@50C +RT 1day
- Test method:

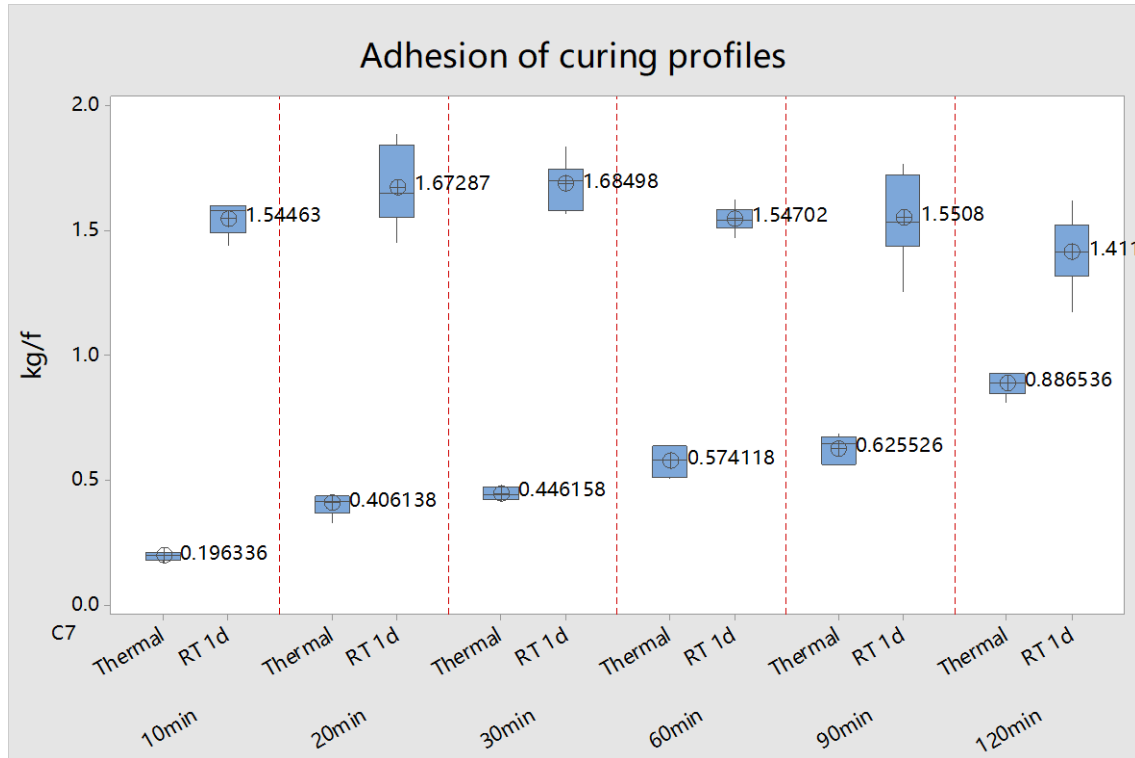


Test flow:



CURING PROFILE STUDY

TEST DATA



Summary

Thermal stage

- With longer thermal baking time, ICP2120 adhesion performs increasing.
- Failure mode: 10-60mins, surface tacky free only, with more than 90mins, ICP 2120 fully cured

Thermal + 1day RT stage

- 30mins + 1day RT group adhesion > others
- All failure mode is cohesive

30mins@50C + 1day RT cure profile as recommendation.

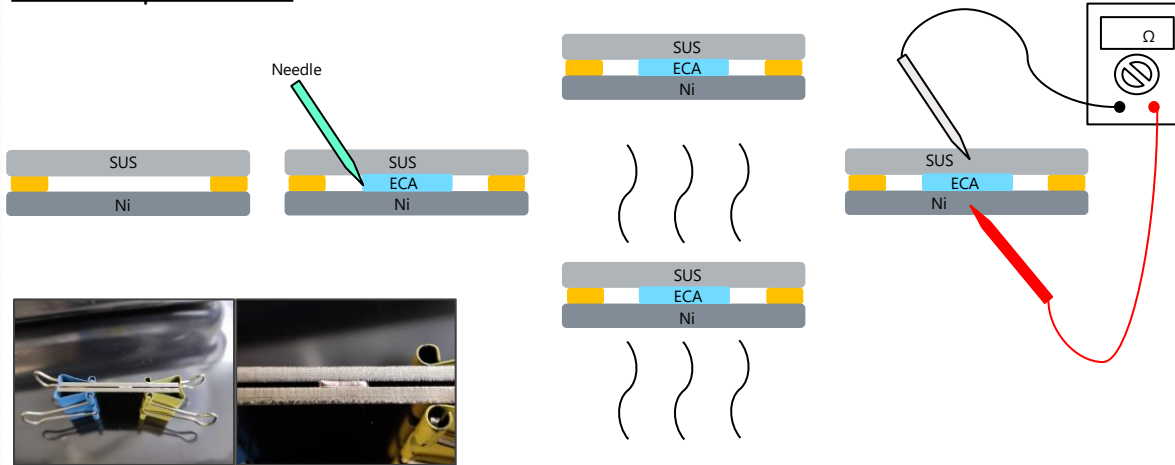
AGENDA

- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test



ADHESIVE DCR(DIRECTLY CONTACT RESISTANT) TEST TEST ENVIRONMENT

DCR test procedure:

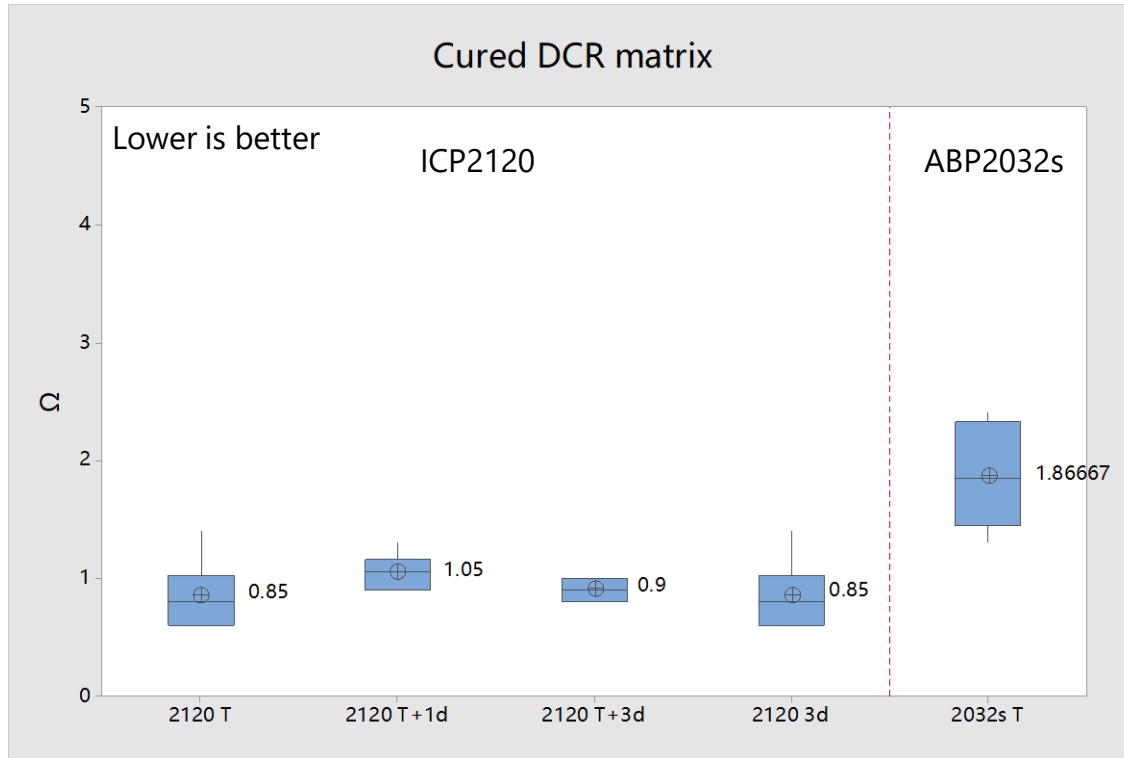


Test parameter:

- Gap size: 500um
- Substrate: SUS/Ni, Ni with plasma
- Adhesive: ICP2120, ABP2032s
- Curing profile:
 - ICP2120: RT 3days, 30mins@50C+RT 1/3days
 - ABP2032s: 1hr@80C
- HTHH(85C85RH%): 5/10 days
- TS(-40C 30mins+85C 30mins /cyc): 5/10 days

ADHESIVE DCR(DIRECTLY CONTACT RESISTANT) TEST

DCR DATA OF CURED

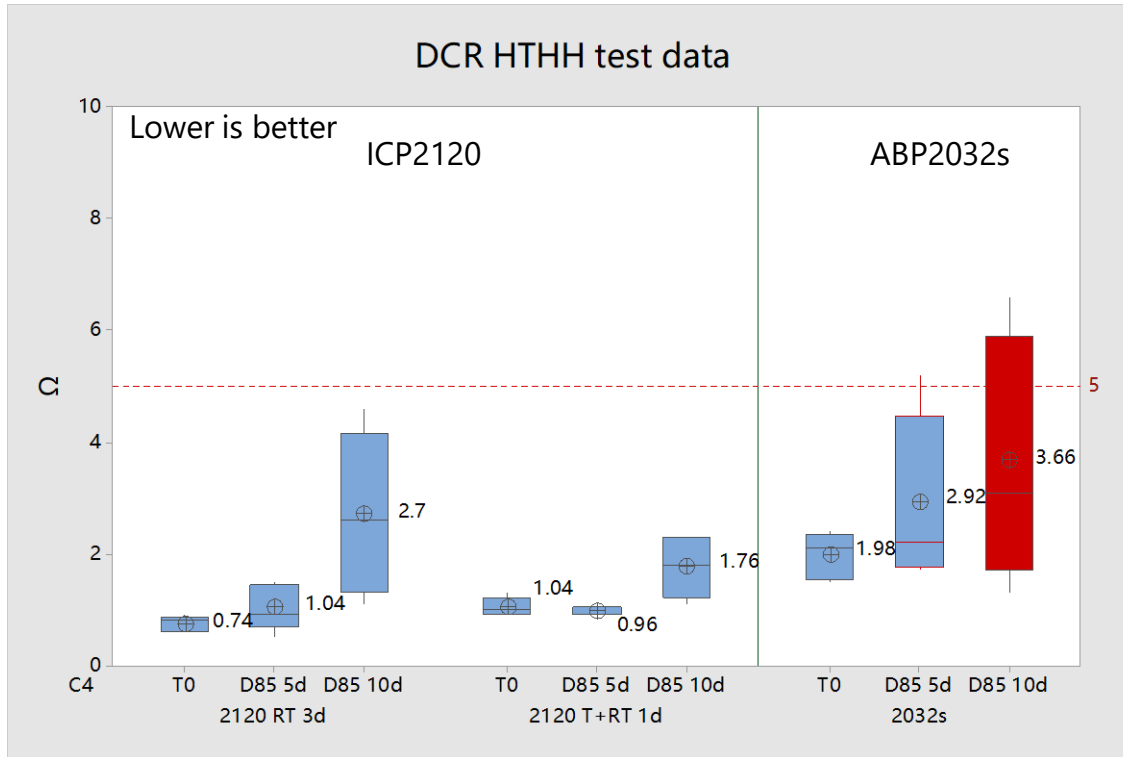


Summary

- 2120T: ICP2120 30mins@50C
- 2120T+1d: ICP2120 30mins@50C+RT 1d
- 2120T+3d: ICP2120 30mins@50C+RT 3d
- 2120 3d: ICP2120 RT 3d
- 2032s T: ABP2032s 1h@80C
- ICP2120 cured DCR all groups $< 5\Omega$, better than ABP2032s.

ADHESIVE DCR(DIRECTLY CONTACT RESISTANT) TEST

DCR DATA POST HTHH

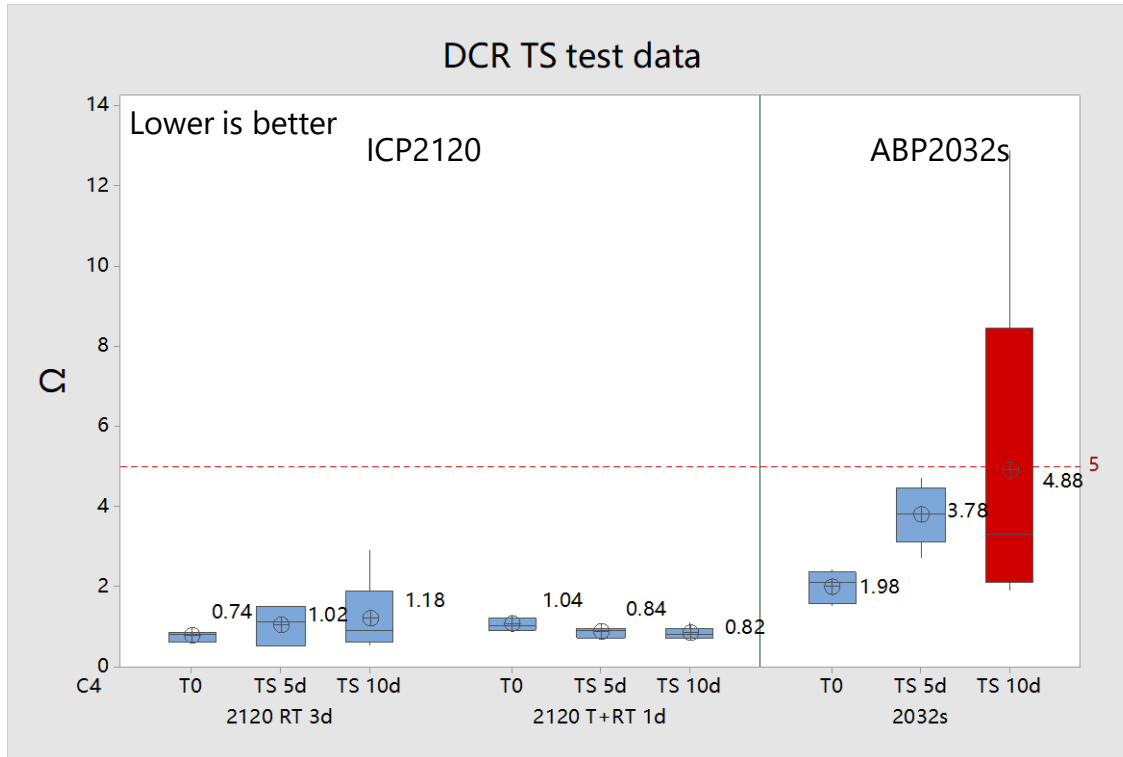


Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120
30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post HTHH 5/10days
 - ICP2120 DCR all groups <5 Ω
 - ABP2032s DCR data turns worse(>5 Ω) from 5days.

ADHESIVE DCR(DIRECTLY CONTACT RESISTANT) TEST

DCR DATA POST TS



Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post TS 5/10days,
 - ICP2120 DCR all groups <5Ω,
 - ABP2032s DCR data turns worse(>5Ω) from 10days.

AGENDA

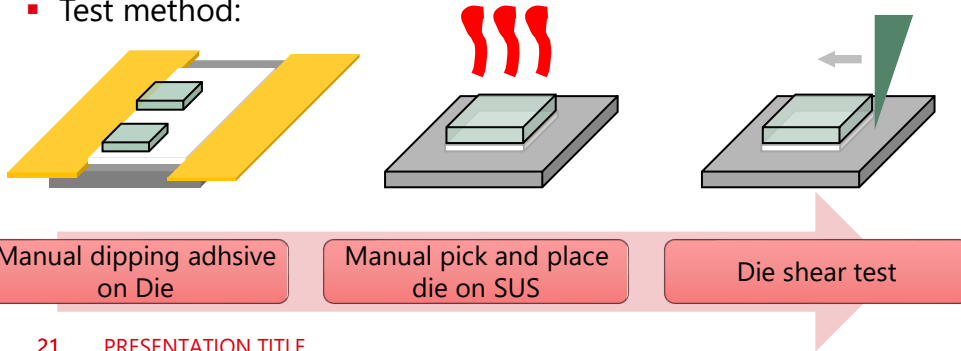
- 01 Material Property
- 02 Work life
- 03 Shore hardness
- 04 Curing profile
- 05 DCR test
- 06 Adhesion test**



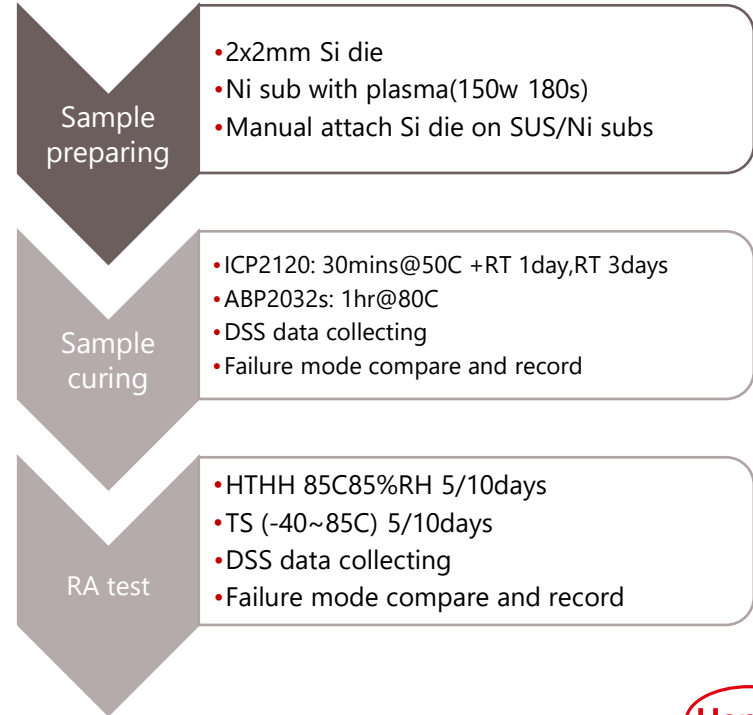
ADHESION PERFORMANCE TEST ENVIRONMENT

Test parameter:

- Die size: 2*2mm Si die(370um thickness)
- Substrate: SUS/Ni, Ni with plasma
- Adhesive: ICP2120, ABP2032s
- Test data: Adhesion with different profiles and failure modes
- Curing profiles: ICP 2120(30mins@50C +RT 1day, RT 3days), ABP2032s(1h@80C)
- RA test: HTHH 85C85%RH 5/10days, TS (-40~85C) 5/10days
- Test method:

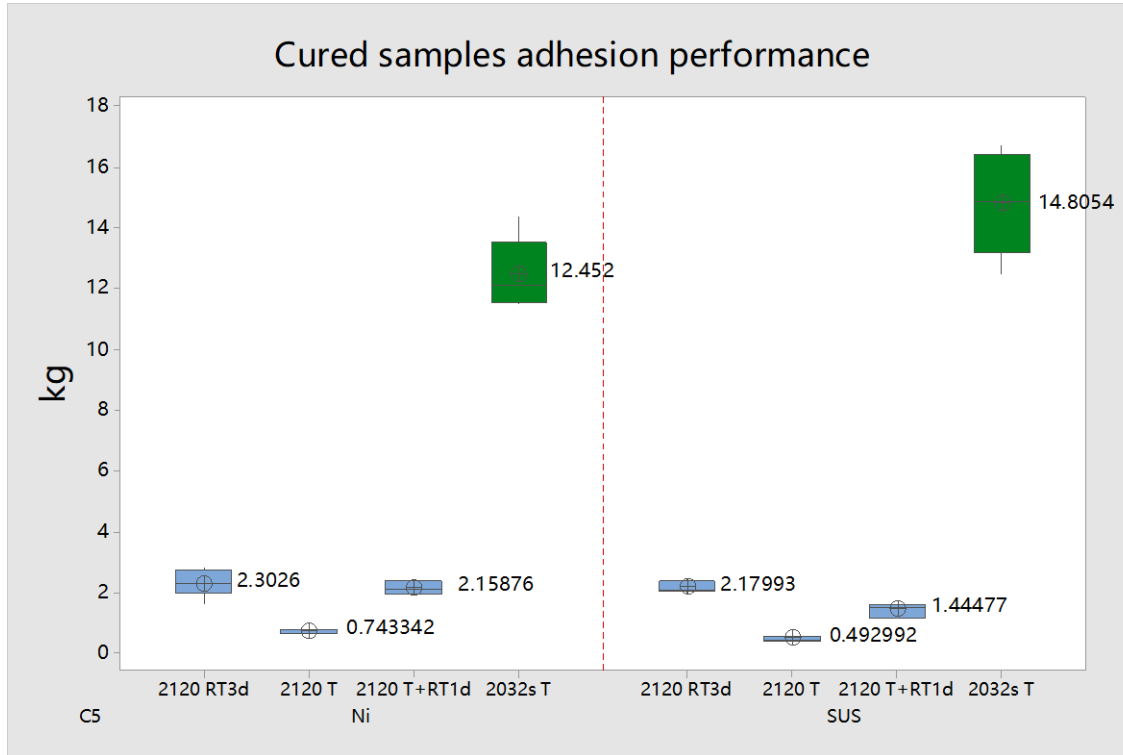


Test flow:



ADHESION PERFORMANCE

CURED SAMPLES ADHESION



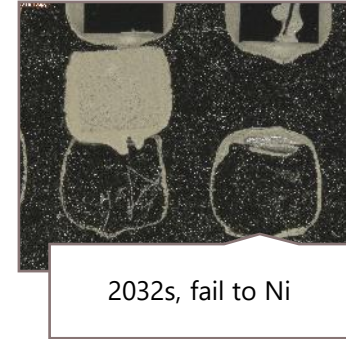
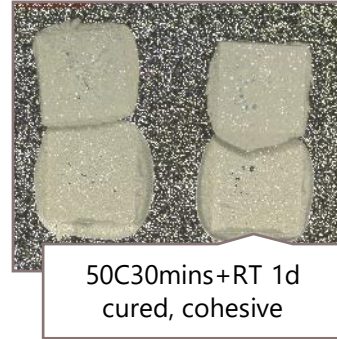
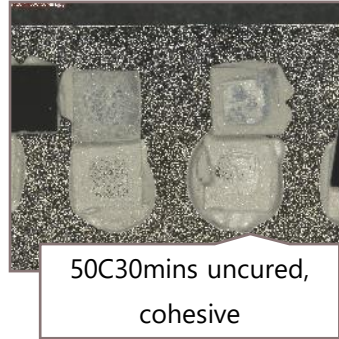
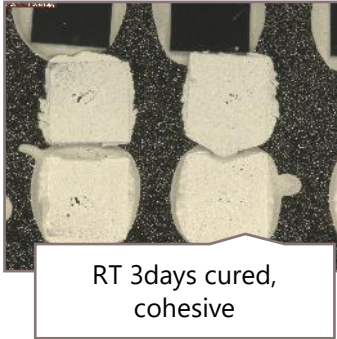
Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T: ICP2120 30mins@50C
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s T: ABP2032s 1h@80C
- ICP2120 on SUS/Ni subs,
 - Cured with thermal only is lower adhesion than other groups
 - Perform better adhesion on Ni subs
- ABP2032s is higher adhesion than ICP2120 on both subs.

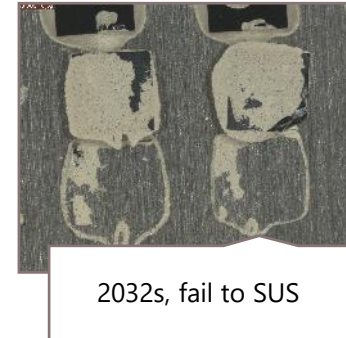
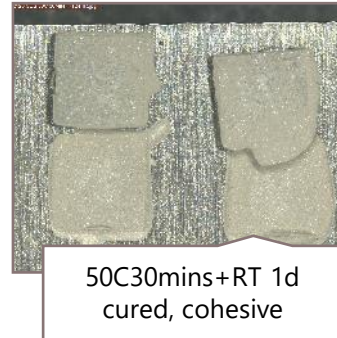
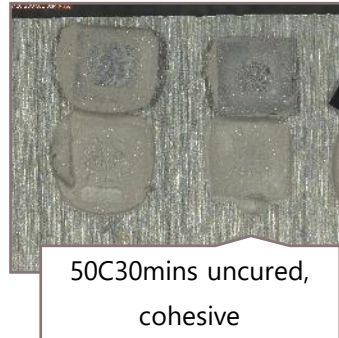
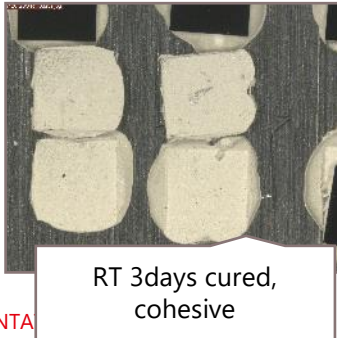
ADHESION PERFORMANCE

FAILURE MODE POST T0

- Ni surface failure mode

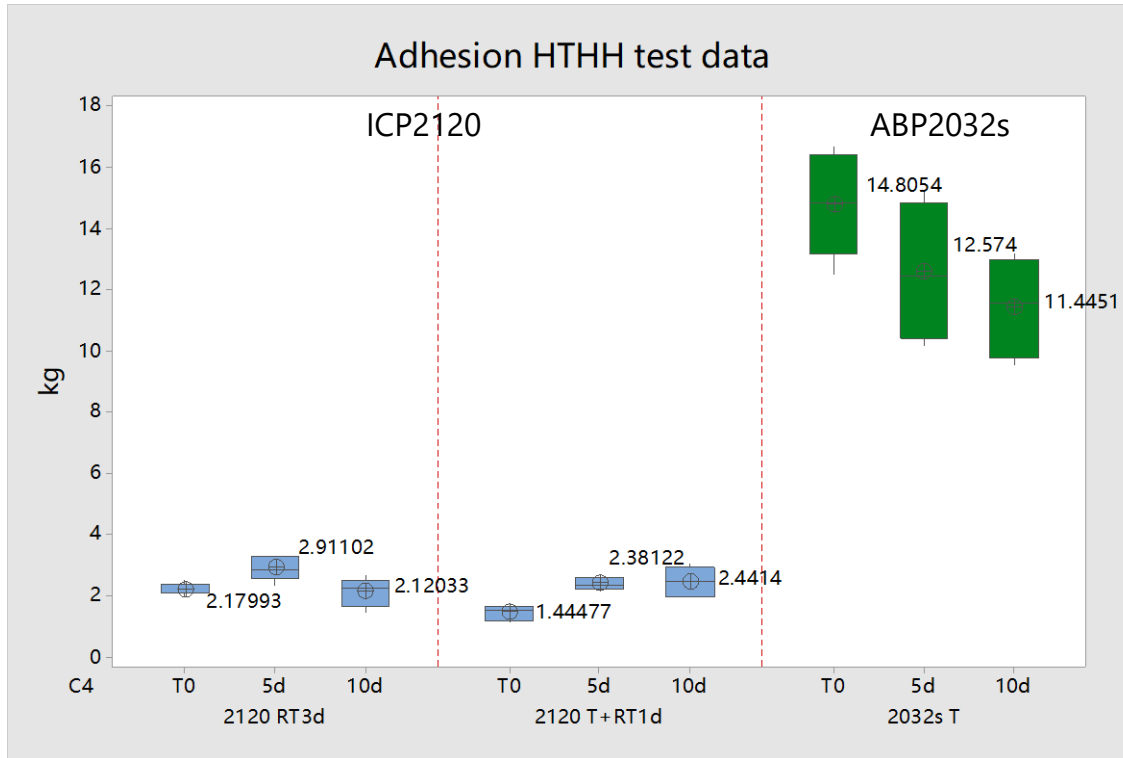


- SUS surface failure mode



ADHESION PERFORMANCE

DSS DATA POST HTHH- SUS SUBSTRATE

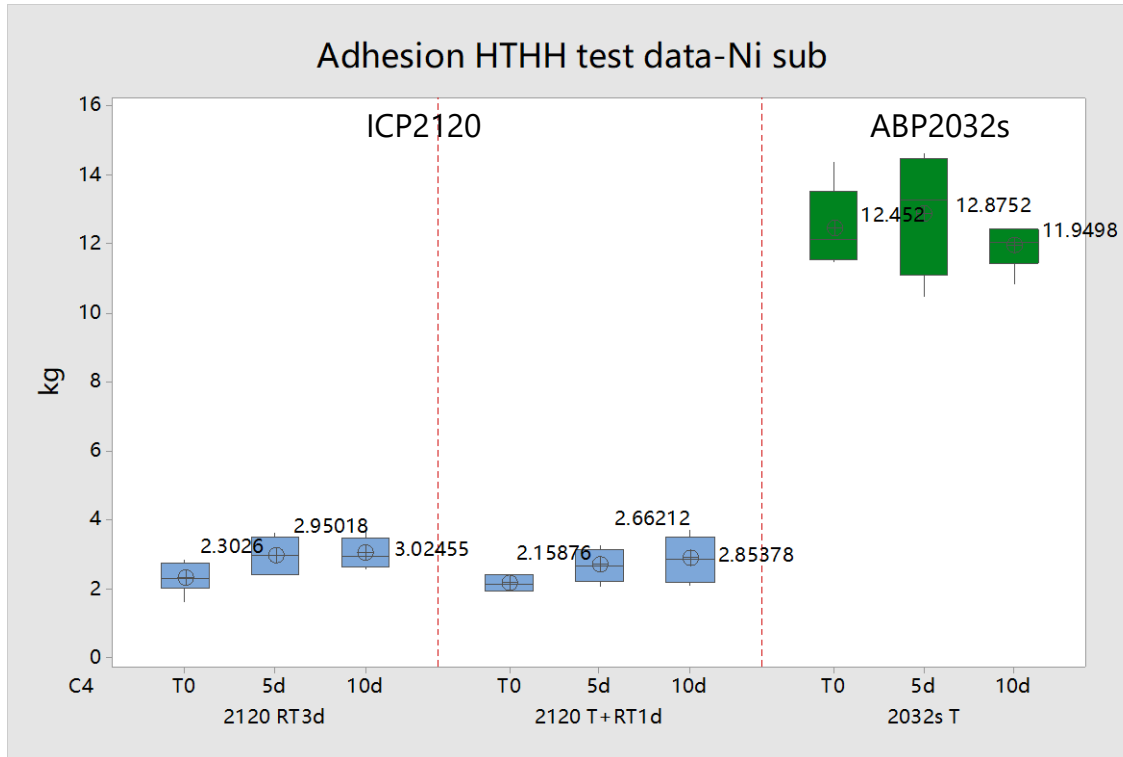


Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post HTHH 5/10days
 - ICP2120 performs post cure phenomenon.
 - ABP2032s adhesion decreases 14% from T0-10days

ADHESION PERFORMANCE

DSS DATA POST HTHH- NI SUBSTRATE



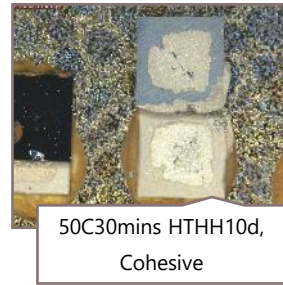
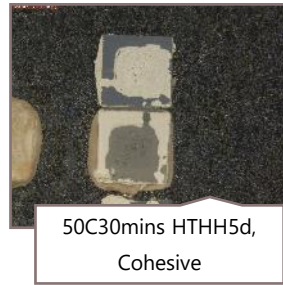
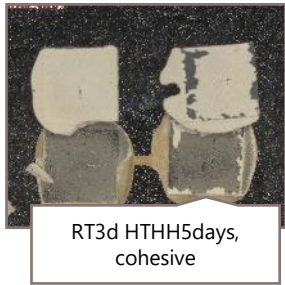
Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post HTHH 5/10days
 - ICP2120 performs post cure phenomenon.
 - ABP2032s adhesion decreases 4% from T0-10days

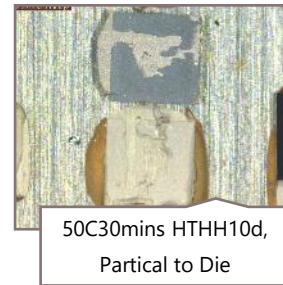
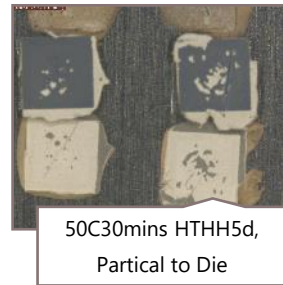
ADHESION PERFORMANCE

FAILURE MODE POST HTHH

- Ni surface failure mode

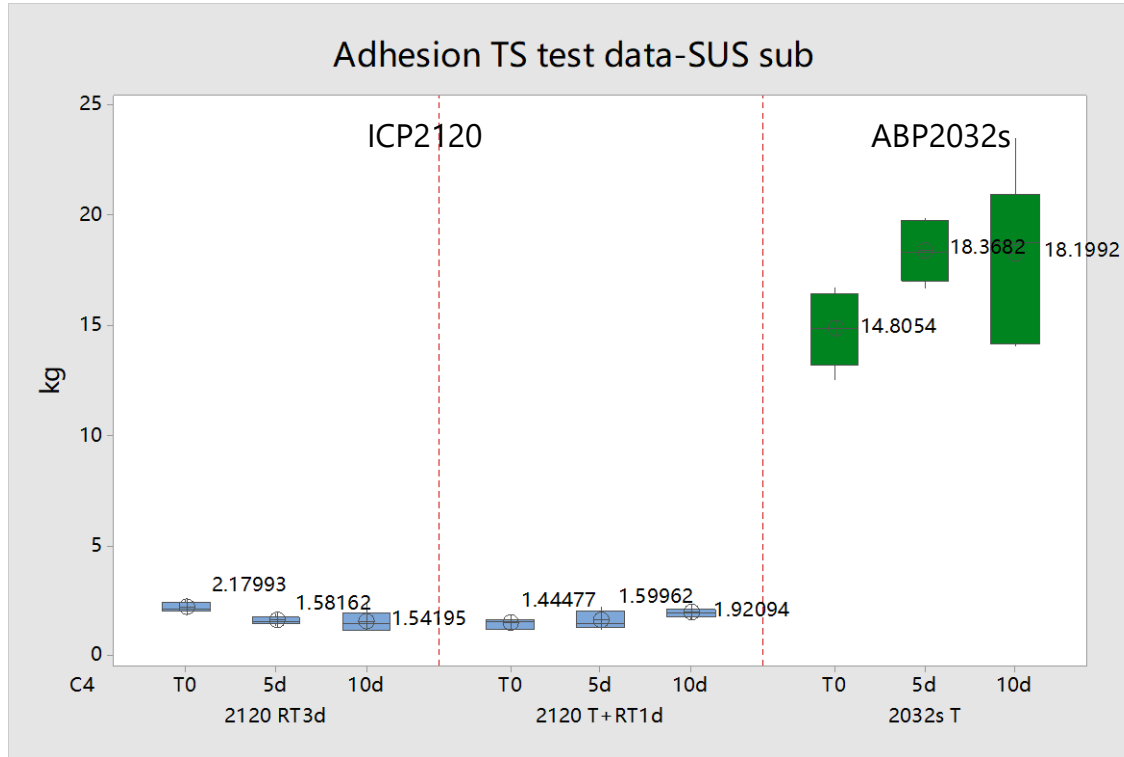


- SUS surface failure mode



ADHESION PERFORMANCE

DSS DATA POST TS- SUS SUBSTRATE

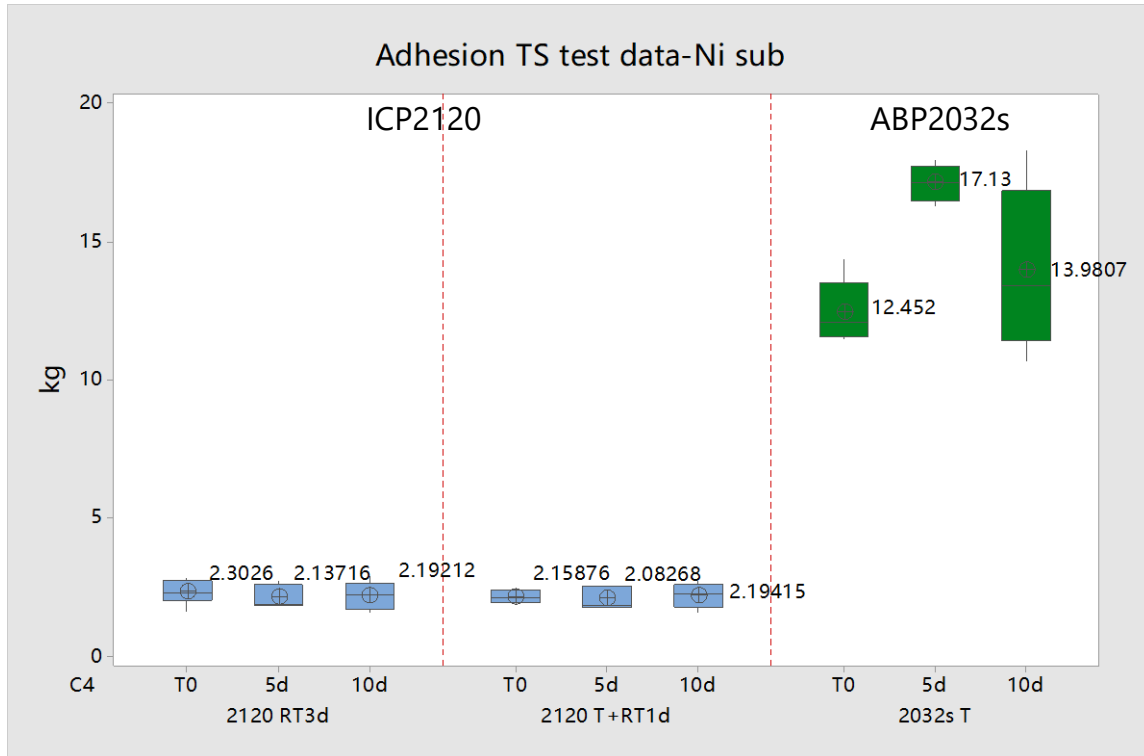


Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post TS 5/10days
 - ICP2120 RT3d performs adhesion attenuation and T+RT1d performs growth
 - ABP2032s adhesion grows 23% from T0-5days and keep stable.

ADHESION PERFORMANCE

DSS DATA POST TS- NI SUBSTRATE



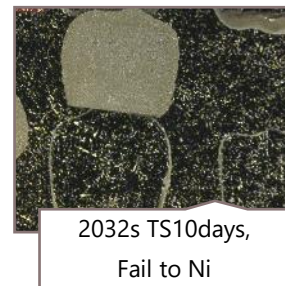
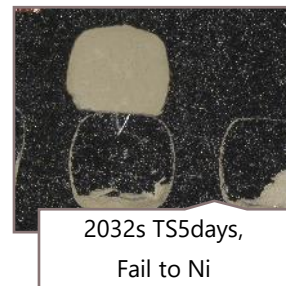
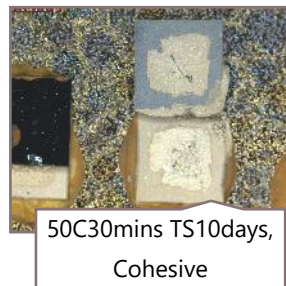
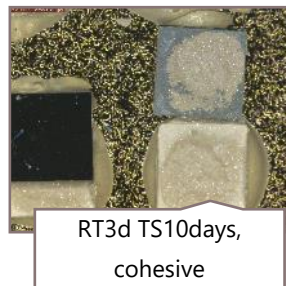
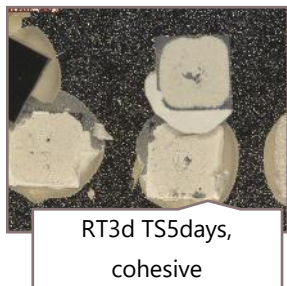
Summary

- 2120 RT 3d: ICP2120 room temp 3days
- 2120T+RT 1d: ICP2120 30mins@50C+room temp 1d
- 2032s: ABP2032s 1h@80C
- Post TS 5/10days
 - ICP2120 RT3d/T+RT1d performs adhesion stable
 - ABP2032s adhesion grows 38% from T0-5days and then drops 18%.

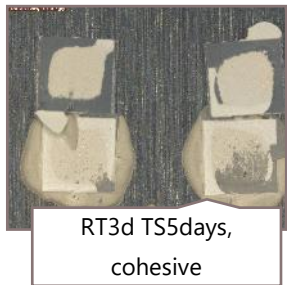
ADHESION PERFORMANCE

FAILURE MODE POST TS

- Ni surface failure mode



- SUS surface failure mode

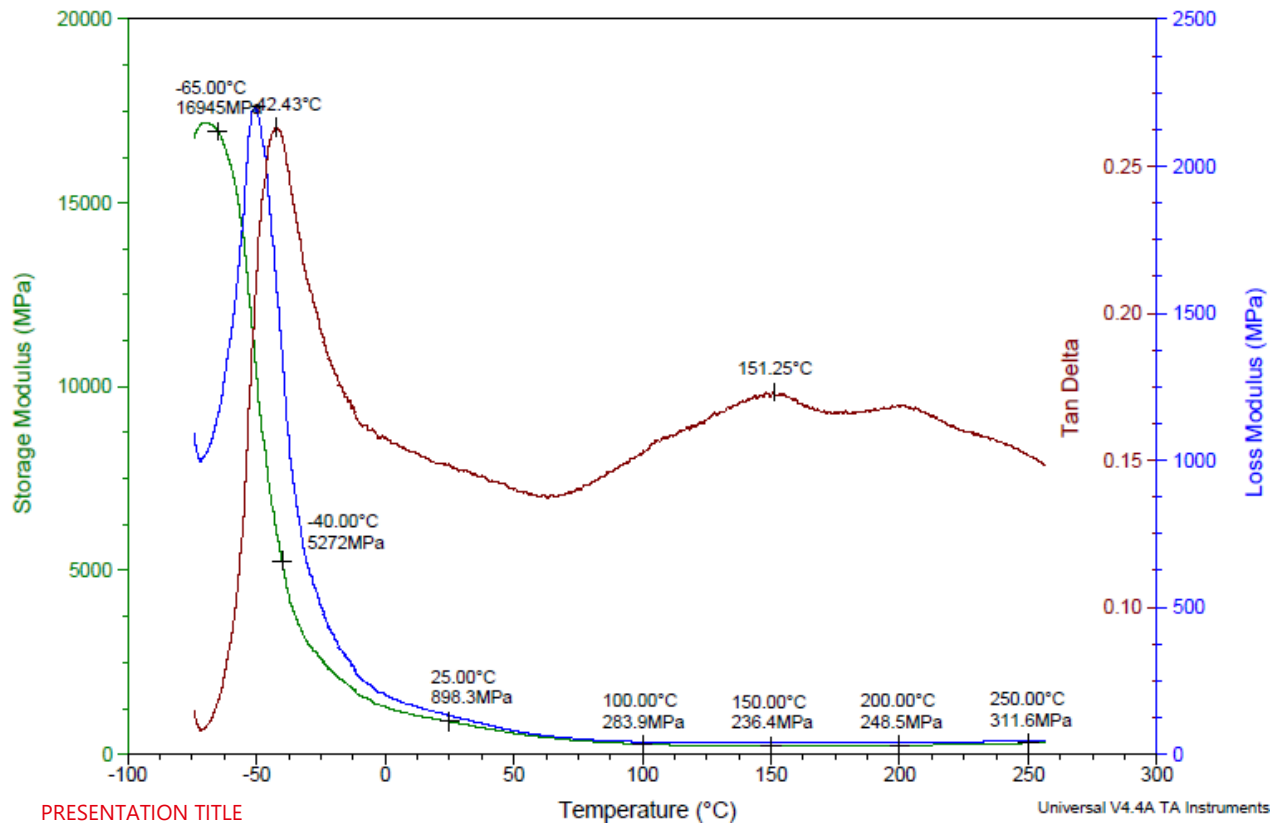


APPENDIX



DMA PROFILE

CURING WITH RT 7DAYS



THANK YOU.

